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SC13115TP

INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>				<i>Complete If Known</i>	
				Application Number	101795,847
				Filing Date	3/18/2004
				First Named Inventor	Da Zhang et al.
				Group Art Unit	2822
				Examiner Name	K. Duong
Sheet	1	of	1	Attorney Docket Number	SC13115TP

NON PATENT LITERATURE DOCUMENTS		
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
KBD	AB	TAN et al., "Effect of degree of amorphization of Si on the formation of titanium silicide," JOURNAL OF APPLIED PHYSICS, VOLUME 91, NUMBER 5, MARCH 1, 2002, pp. 2842-2846.

Examiner Signature		Date Considered	9/17/2005
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation, if not in conformance and not considered. Include copy of this form with next communication to applicant.

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